

Method and Apparatus for Aerial Image Improvement in Projection Lithography Using a Phase Shifting Aperture

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Abstract

A plate 50 for projection lithography comprising a first opaque region 54 located at the center of the plate 50 and a second opaque region 56 formed at the outer edge 52 of the plate. The first and second opaque regions define a light transmissive annular region 58. The annular region 58 comprises a first light transmissive area 60, 62 that imparts a first phase shift to light passing therethrough and a second light transmissive area 64, 66, which imparts a second phase shift to light passing therethrough.

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